

Amendments to the Specification

Please replace the paragraph [0049] with the following amended paragraph:

[0049] FIG. 11B is a representation of a cross-sectional view of the suspended structure 155 of FIG. 11A. Formed on the suspended structure 155 is an upper silica waveguide ~~160~~ 150. A silica or oxide layer 156 is formed on the bottom of the suspended structure 155. By proper selection of the geometry, size and thickness of the layer 156, a simple and uniform layer 156 (e.g., a thermal distortion offset structure) can be tailored to cancel the thermal effect of the patterned waveguides 157 on the opposite side of the suspended structure 155. Beneficially, this technique uses simple geometric patterns that can be made by lithography in a cavity for balancing thermal effects. The addition of a layer 156 permits one to cancel thermal effects without requiring the formation of precisely matching waveguides. The detailed optimization of the geometry of the layer 156 required to cancel the thermal distortion of the rest of the suspended structure 155 can be achieved using FEA or other simulation tools.